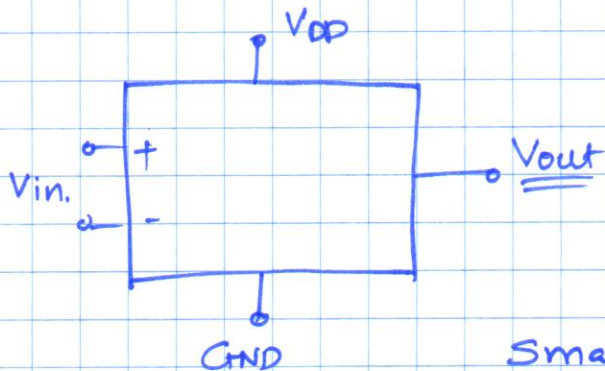


24 September 2019

## Power Supply Rejection Ratio PSRR

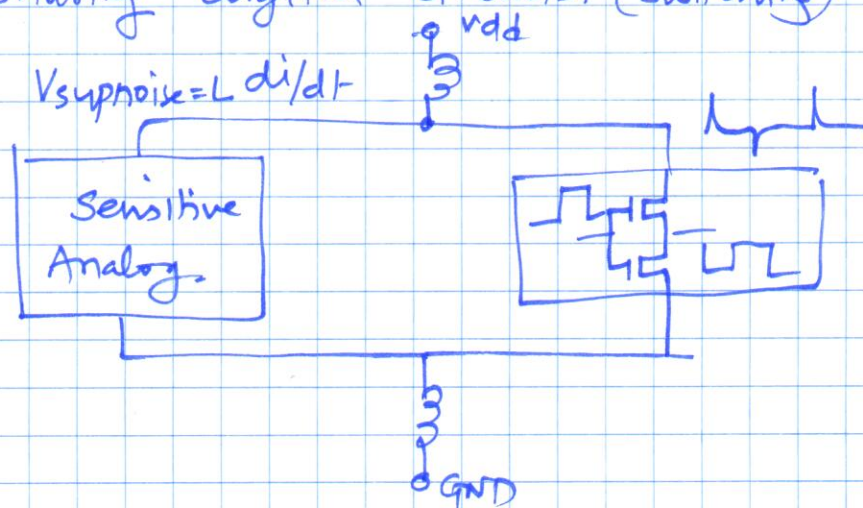


Supply noise either on  $V_{DD}$  or  $GND$  can leak into  $V_{out}$  - limiting

smallest signal we can detect.

### Source of Supply noise

- \* Off-chip noise electrically coupled through pins
- \* Noise of  $V_{DD}$  (regulators - switching power supplies)
- \* Noise coupled through  $V_{DD}/GND$  bondwires sharing digital circuits. (switching)

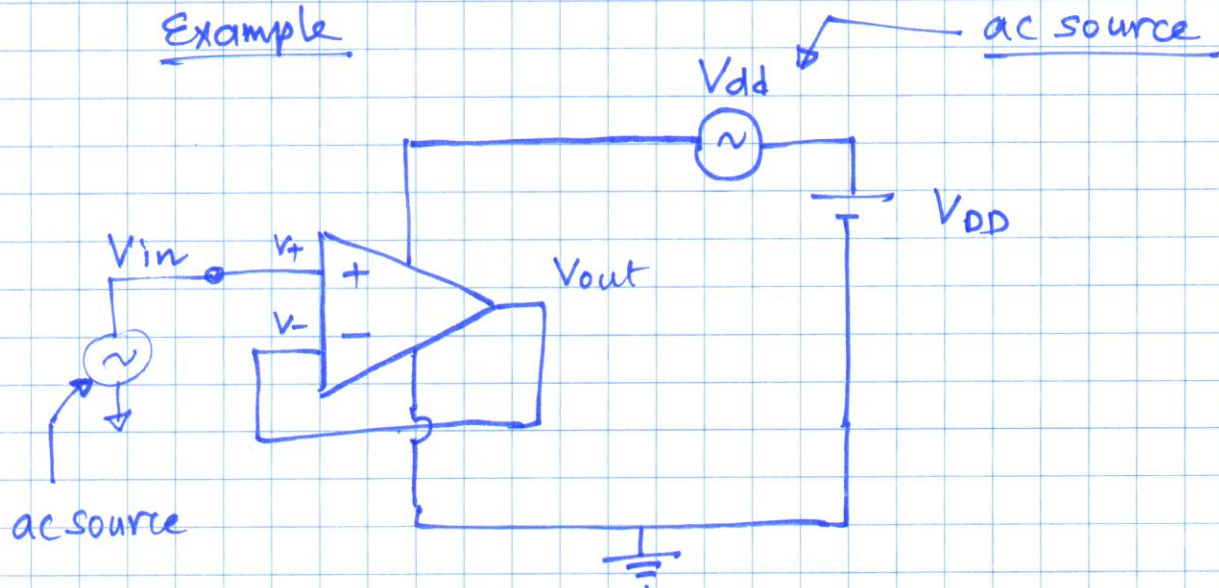


$$PSRR \text{ (definition)} = \frac{A_{dm} (\nu_{VDD} \text{ or } \nu_{GND=0})}{A_{ps} (\nu_{in}=0)}$$

$A_{ps}$  = AC gain from  $V_{DD}$  or  $GND$  to  $V_{out}$  when  $\nu_{in}=0$ .

## Measuring PSRR

### Example



To calculate gain from  $V_{DD}$  to  $V_{out}$   $V_{in} = 0$

$$V_{out} = A_{PSV_{DD}} V_{DD} + A_{dm}(V_{+} - V_{-})$$

$$V_{out} = A_{PSV_{DD}} V_{DD} + A_{dm}(0 - V_{out})$$

$$V_{out}(1 + A_{dm}) = A_{PSV_{DD}} V_{DD}$$

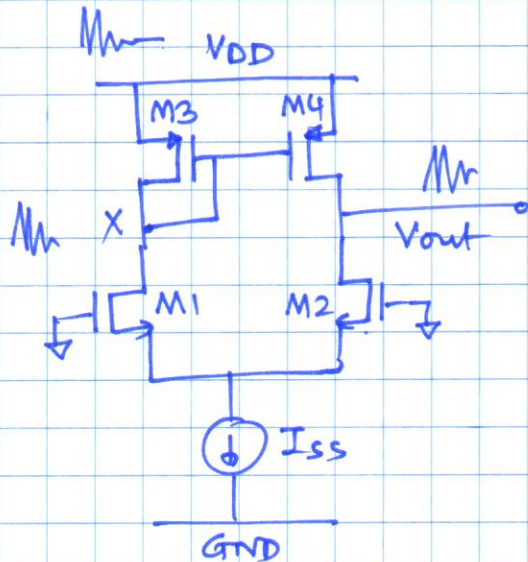
$$\frac{V_{out}}{V_{DD}} = \frac{A_{PSV_{DD}}}{(1 + A_{dm})} \approx \frac{A_{PSV_{DD}}}{A_{dm}} = \frac{1}{PSRR}$$

Caution: During PSRR measurements, make sure all biasing circuits are included.





## Insights on PSRR

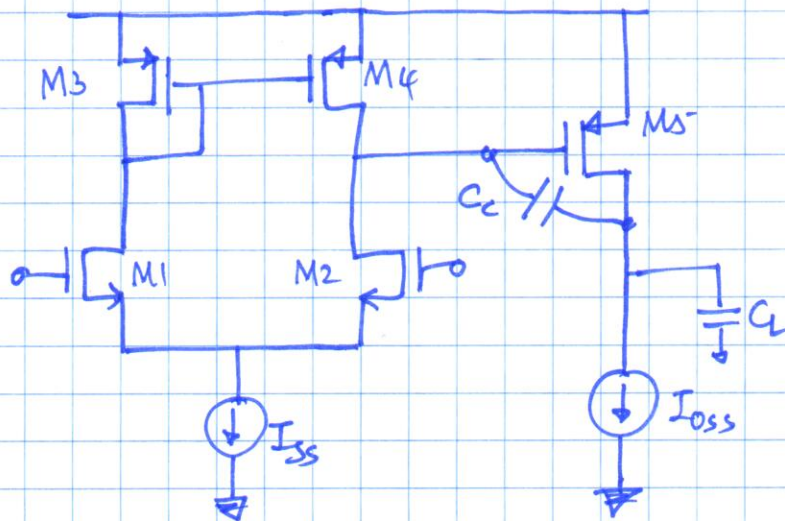


unity gain from  $V_{DD}$  to  $V_{out}$

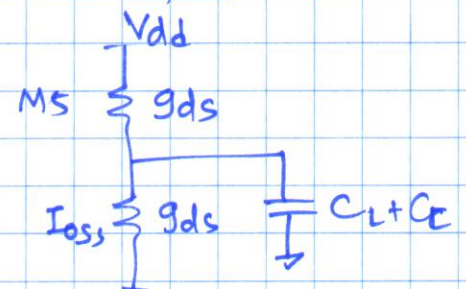
$$A_{PSVDD} = 1$$

$$\therefore PSRR = \frac{g_{mN} r_{out}}{1}$$

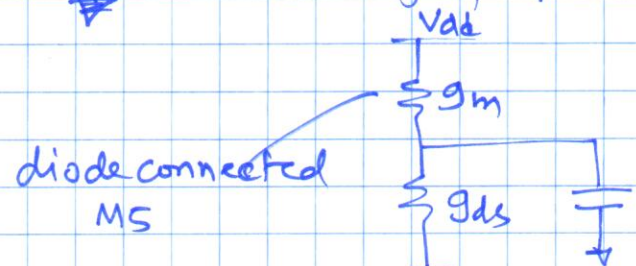
## Two Stage OTA



@ Low frequency



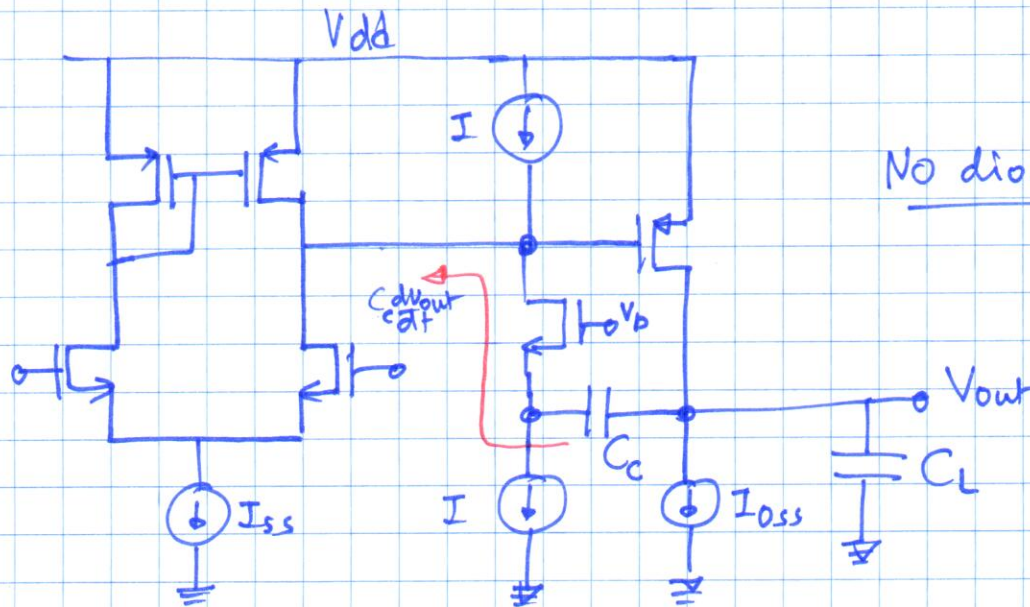
@ High frequencies



Poor PSRR @ High frequencies.

To improve High freq. PSRR —  $C_c$  decoupling from  $V_{dd}$ .

How?



No diode @ HF.

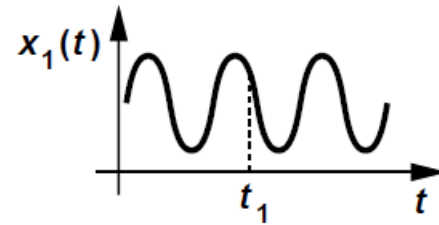
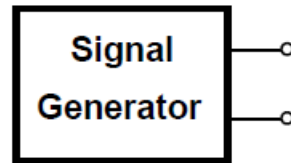
**LECTURE 14**

**24 September 2019**

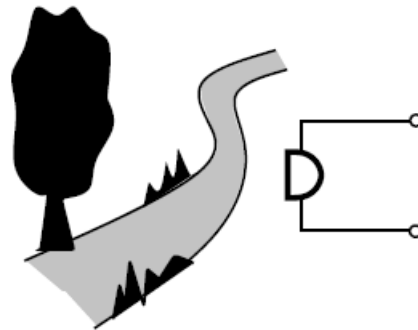
# **NOISE**

**Lecture Notes adapted from Chapter 7  
B. Razavi (Design of Analog CMOS ICs)**

# Statistical Characteristics of Noise

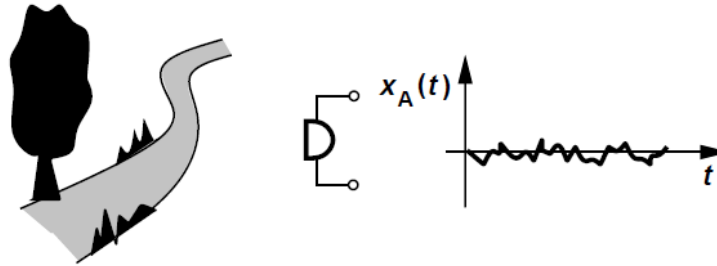


(a)

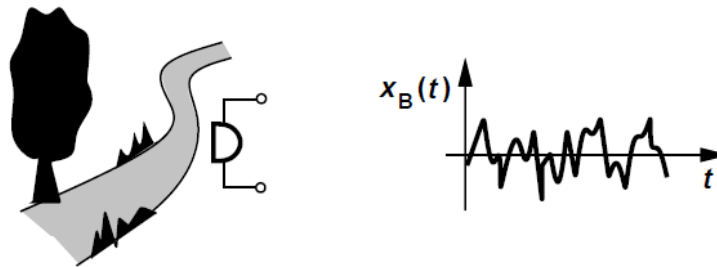


- Noise - random process
- Noise is everywhere
- $x_1(t_1)$  &  $x_2(t_2)$  - Difference between deterministic and random
- Noise(t) unpredictable
- Noise can't be calibrated out

# Statistical Characteristics of Noise



(a)

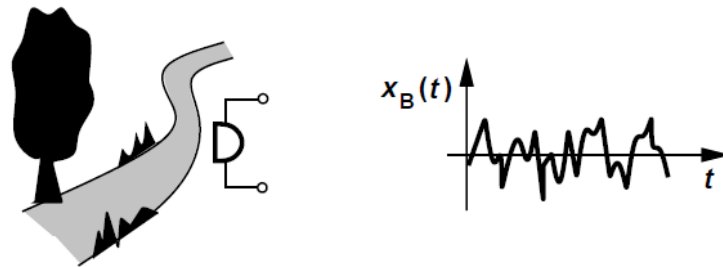
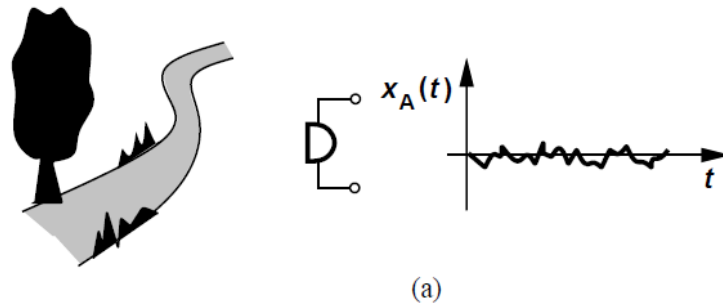


- Average power of noise is predictable
- Average power delivered by a periodic voltage  $v(t)$  with period  $T$  to a load resistance  $R_L$  is defined as

$$P_{av} = \frac{1}{T} \int_{-T/2}^{+T/2} \frac{v^2(t)}{R_L} dt$$



# Statistical Characteristics of Noise



- **Random signal (aperiodic): measurement over a long time**

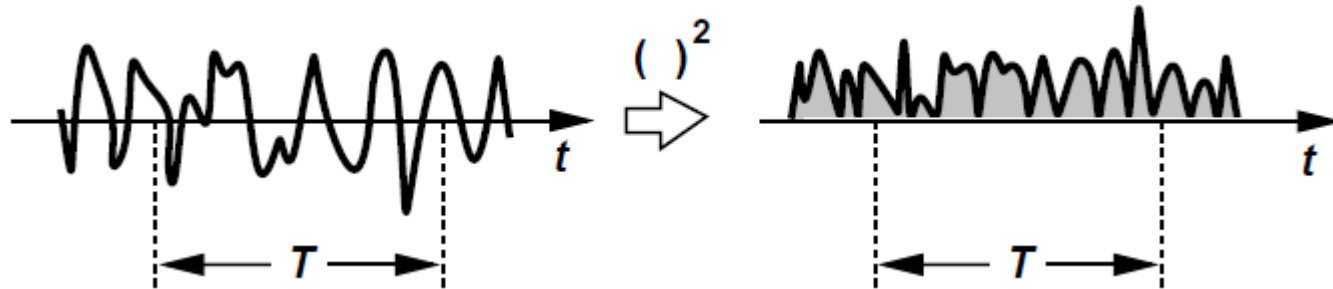
$$P_{av} = \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} \frac{x^2(t)}{R_L} dt$$

- **$x_B(t)$  delivers more power than  $x_A(t)$**



# Statistical Characteristics of Noise

- To calculate average power of (noise) signal  $x(t)$



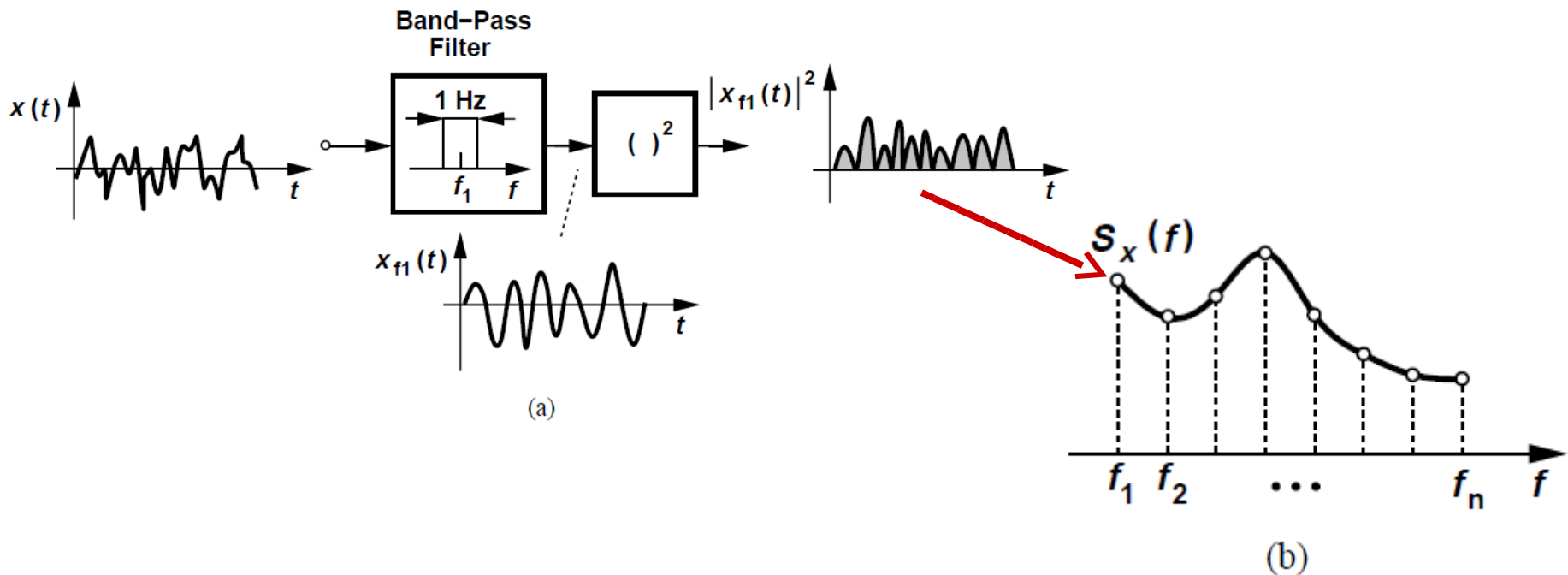
- $P_{av}$  is defined as

$$P_{av} = \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} x^2(t) dt$$

- $P_{av}$  is expressed in  $V^2$  rather than  $W$
- RMS voltage for noise can be defined as  $\sqrt{P_{av}}$

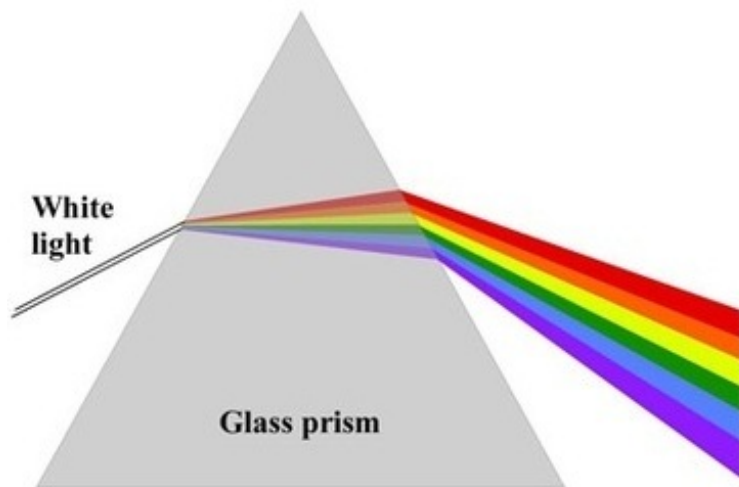
# Noise Spectrum

- Power Spectral Density (PSD)  $S_x(f)$ 
  - signal power at each frequency
- $S_x(f)$  defined as the average power carried by  $x(t)$  in a 1-Hz bandwidth around  $f$

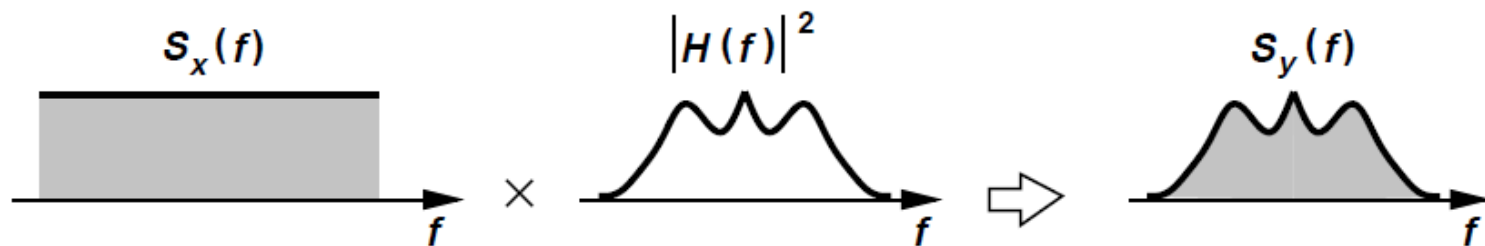
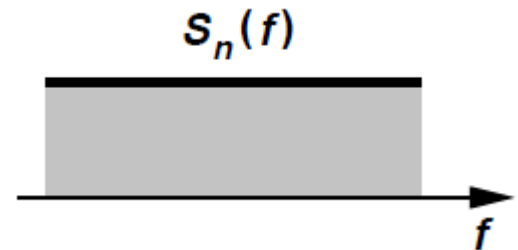


# Noise Spectrum

- $S_x(f)$  --  $V^2/\text{Hz}$  or  $V/\sqrt{\text{Hz}}$
- white noise PSD -- Noise spectrum that is flat *in the band of interest* is usually called white

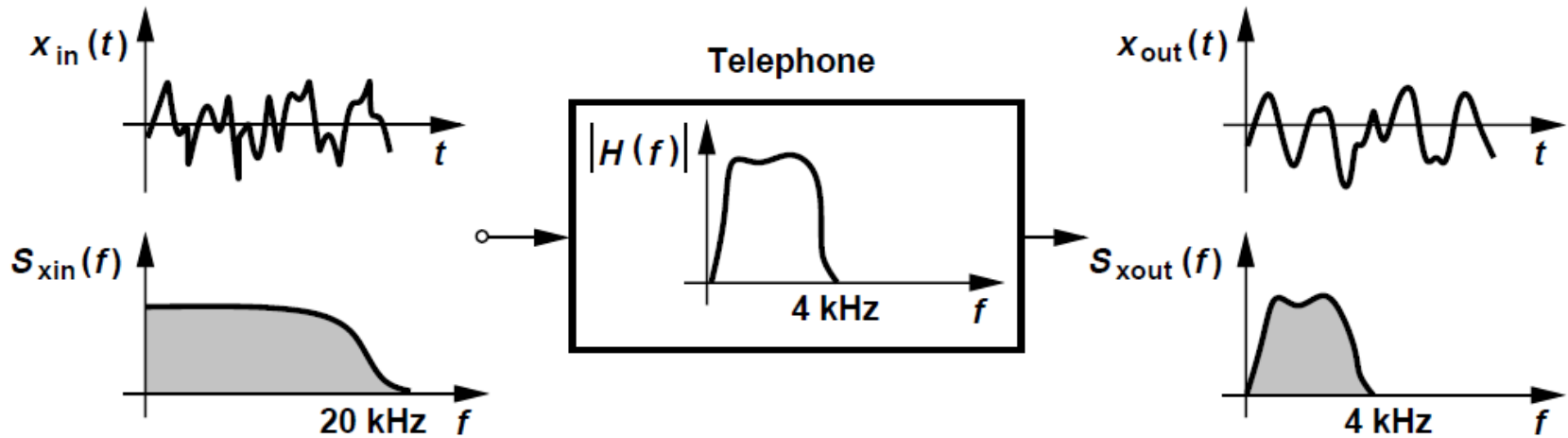


Color	$\lambda$ (nm)	Freq (Hz)
Red	760-647	$4.3 \times 10^{14}$
Orange	647-585	$4.3 \times 10^{14}$
Yellow	585-575	$5.2 \times 10^{14}$
Green	575-491	$5.6 \times 10^{14}$
Blue	491-424	$6.6 \times 10^{14}$
Violet	424-380	$7.3 \times 10^{14}$



$$S_Y(f) = S_x(f)|H(f)|^2$$

# Telephone Example



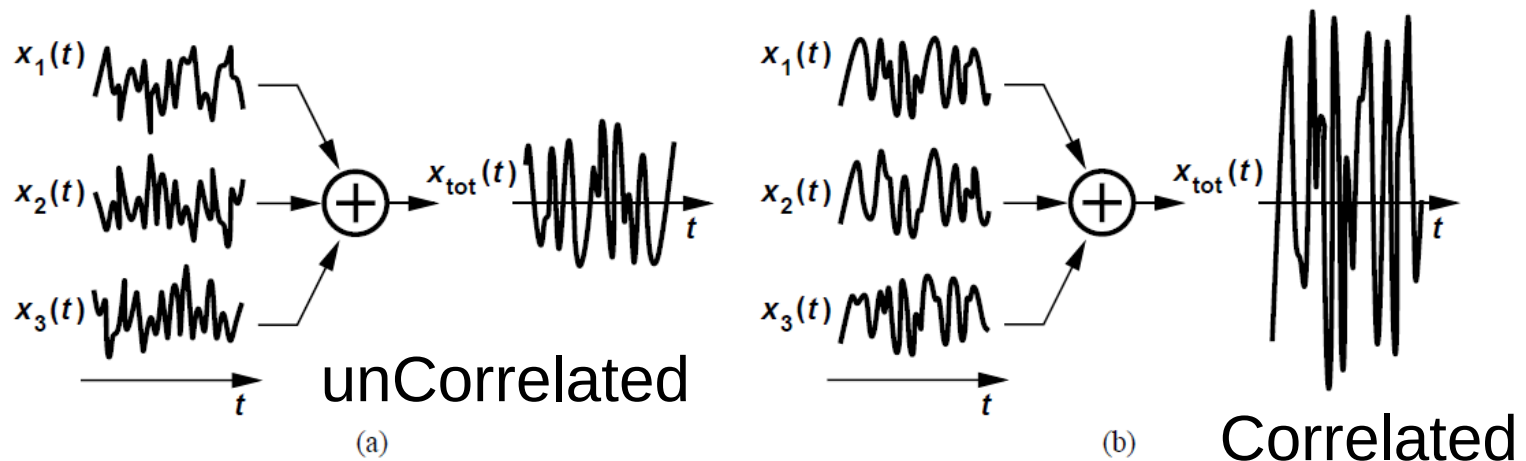


# Correlated vs Uncorrelated Sources

- Superposition Principle not suitable for random noise signals
- Average noise power

$$\begin{aligned}P_{av} &= \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} [x_1(t) + x_2(t)]^2 dt \\&= \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} x_1^2(t) dt + \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} x_2^2(t) dt \\&\quad + \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} 2x_1(t)x_2(t) dt \\&= P_{av1} + P_{av2} + \lim_{T \rightarrow \infty} \frac{1}{T} \int_{-T/2}^{+T/2} 2x_1(t)x_2(t) dt, \quad \text{red arrow correlation}\end{aligned}$$

## Stadium Noise



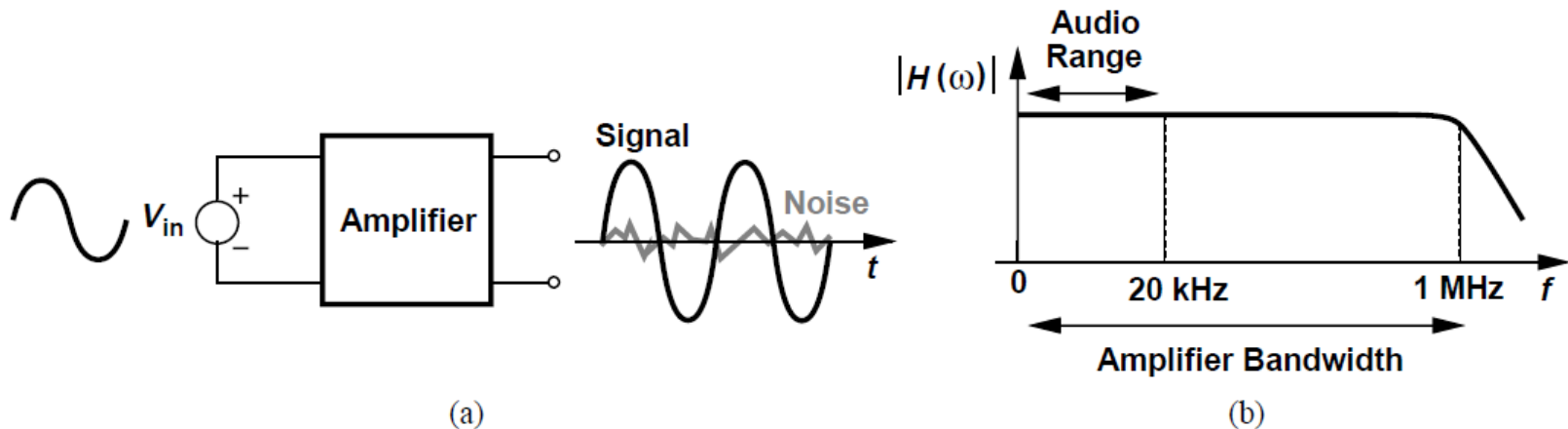
# Signal-to-Noise Ratio (SNR)

- SNR – intelligibility of the signal

$$\text{SNR} = \frac{P_{sig}}{P_{noise}}$$

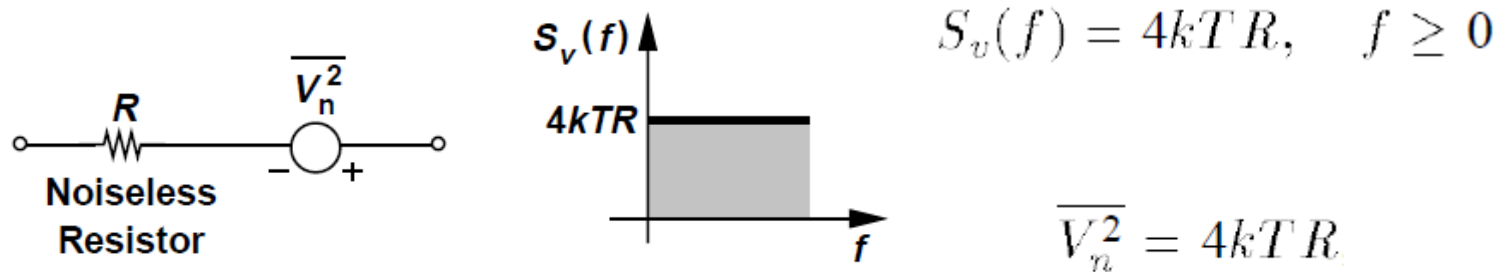
- For a sinusoid with peak amplitude  $A$ ,  $P_{sig} = A^2/2$
- Noise Power

$$P_{noise} = \int_{-\infty}^{+\infty} S_{noise}(f) df.$$



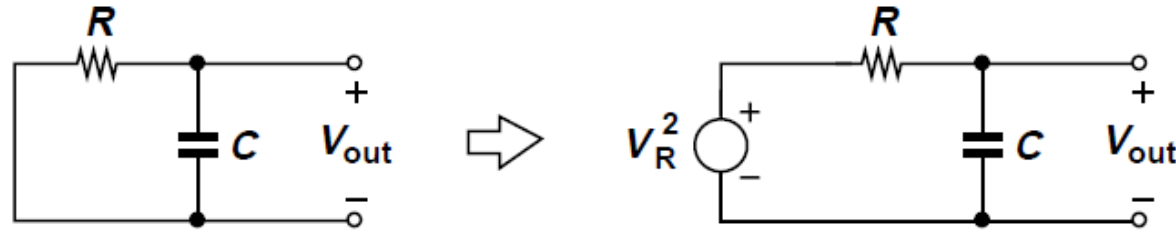
# Resistor Thermal Noise

- Random motion of electrons in a conductor induces fluctuations in the voltage measured across it even though the average current is zero



- $k = 1.38 \times 10^{-23}$  J/K is the Boltzmann constant
- $1000 \, \Omega$  (300 K)  $\rightarrow 16 \times 10^{-18} \text{ V}^2/\text{Hz}$ , or 4 nV/ $\sqrt{\text{Hz}}$

# Resistor Thermal Noise: Example



Noise spectrum and total noise power in  $V_{out}$

$$\frac{V_{out}}{V_R}(s) = \frac{1}{RCs + 1}$$

$$S_{out}(f) = S_v(f) \left| \frac{V_{out}}{V_R}(j\omega) \right|^2$$

$$P_{n,out} = \int_0^\infty \frac{4kTR}{4\pi^2 R^2 C^2 f^2 + 1} df$$

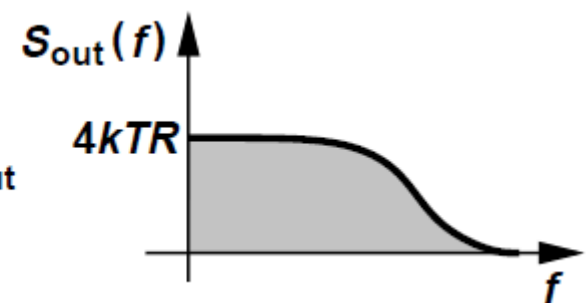
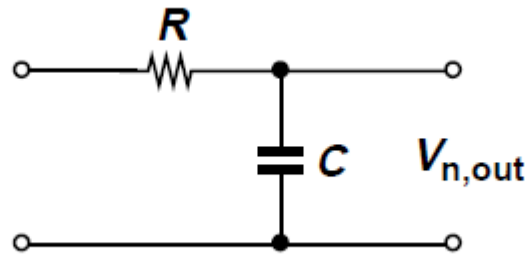
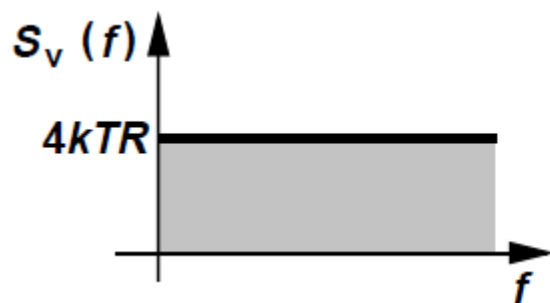
$$= 4kTR \frac{1}{4\pi^2 R^2 C^2 f^2 + 1}$$

Put  $2\pi RCf = u$

$$P_{n,out} = \frac{2kT}{\pi C} \int_0^\infty \frac{du}{u^2 + 1}$$

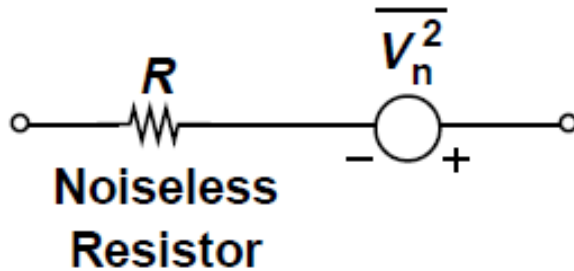
$$P_{n,out} = \frac{2kT}{\pi C} \tan^{-1} u \Big|_{u=0}^{u=\infty}$$

$$= \frac{kT}{C}$$



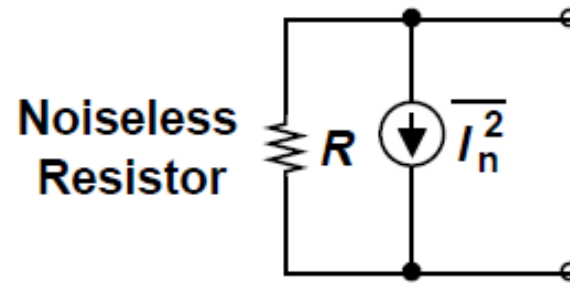


# Resistor Thermal Noise



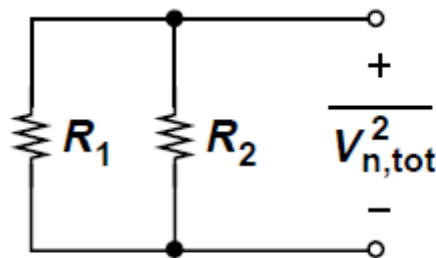
$$\overline{V_n^2} = 4kTR$$

$$V^2/\text{Hz}$$

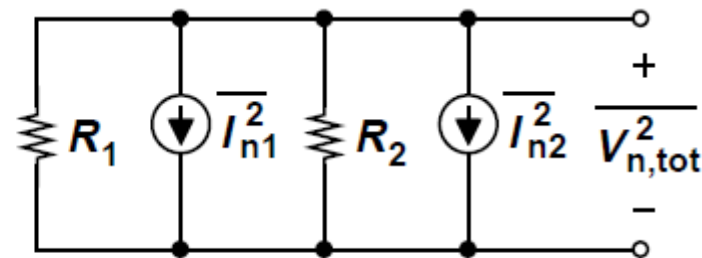


$$\overline{I_n^2} = 4kT/R$$

$$A^2/\text{Hz}$$



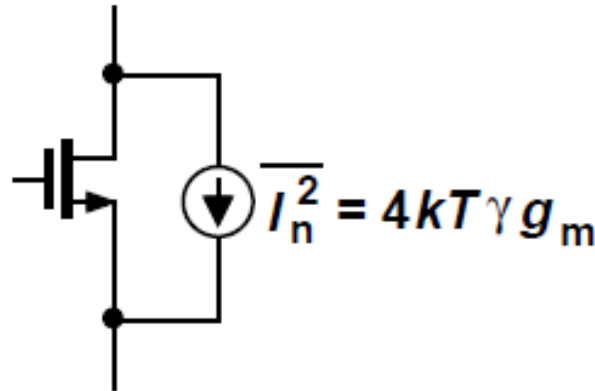
$$\begin{aligned}\overline{I_{n,tot}^2} &= \overline{I_{n1}^2} + \overline{I_{n2}^2} \\ &= 4kT \left( \frac{1}{R_1} + \frac{1}{R_2} \right)\end{aligned}$$



$$\begin{aligned}\overline{V_{n,tot}^2} &= \overline{I_{n,tot}^2} (R_1 || R_2)^2 \\ &= 4kT (R_1 || R_2),\end{aligned}$$

# MOSFET Thermal Noise

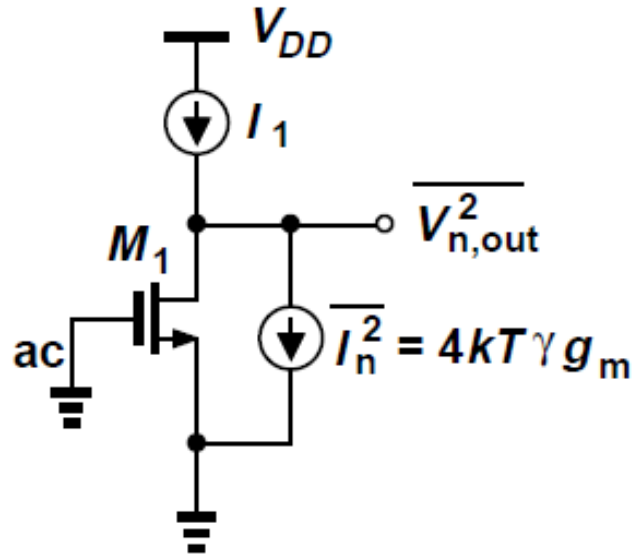
- The Thermal noise generated in the channel
- For long-channel MOS devices operating in saturation,



$\gamma$  (*Excess Noise Coefficient*) = 2/3 for long-ch transistors  
2-3 for short-ch transistors

Short channel device – Ecritical – Velocity saturation – extra work done by Efield – dissipation → Noise ^

# MOSFET Thermal Noise: Example

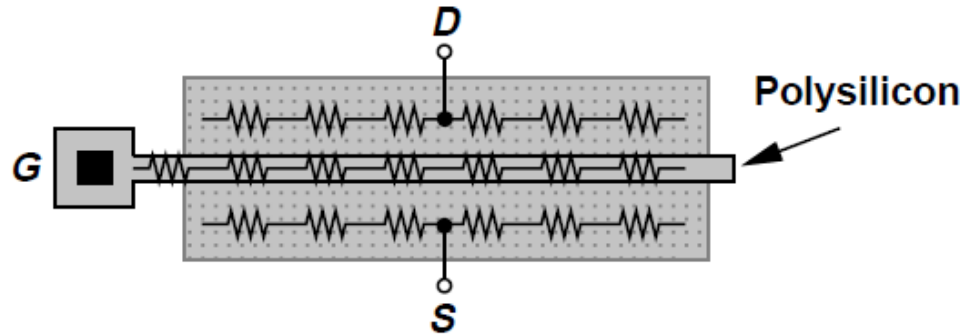


$$S_{out}(f) = S_{in}(f)|H(f)|^2$$

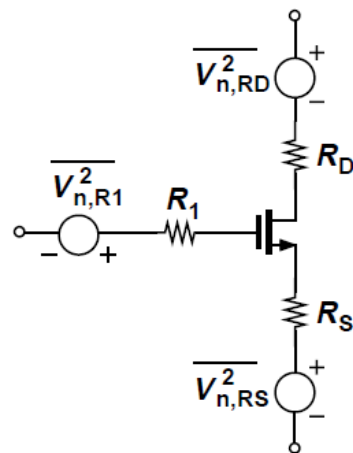
$$\begin{aligned}\overline{V_n^2} &= \overline{I_n^2} r_O^2 \\ &= (4kT\gamma g_m) r_O^2\end{aligned}$$

- Input is set to zero for noise calculation
- The output resistance  $r_o$  does not produce noise because it is not a physical resistor

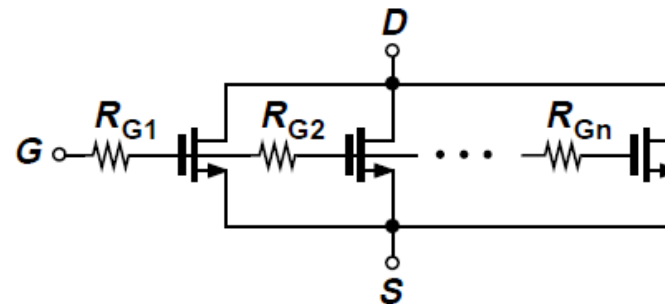
# MOSFET Thermal Noise



(a)



(b)

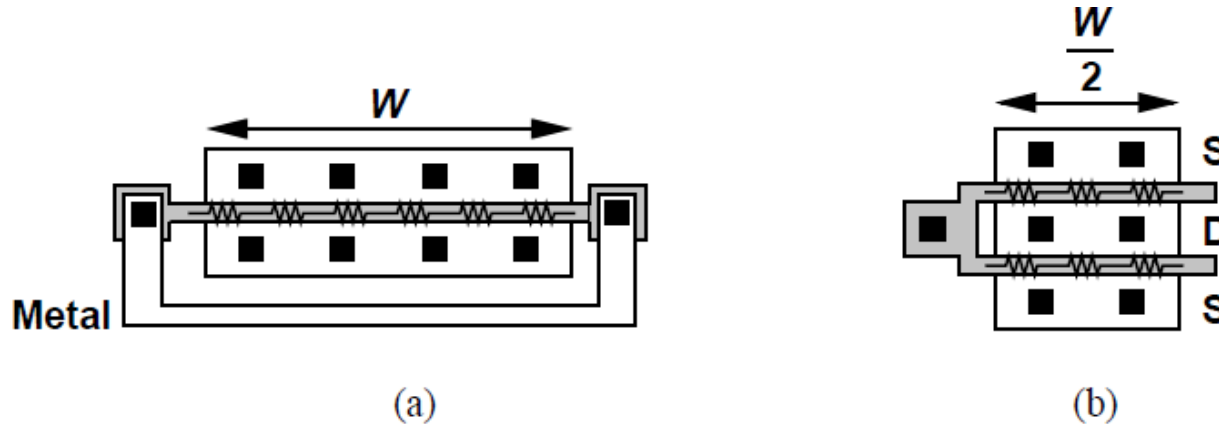


$$R_{G1} + R_{G2} + \dots + R_{Gn} = R_G$$

(c)

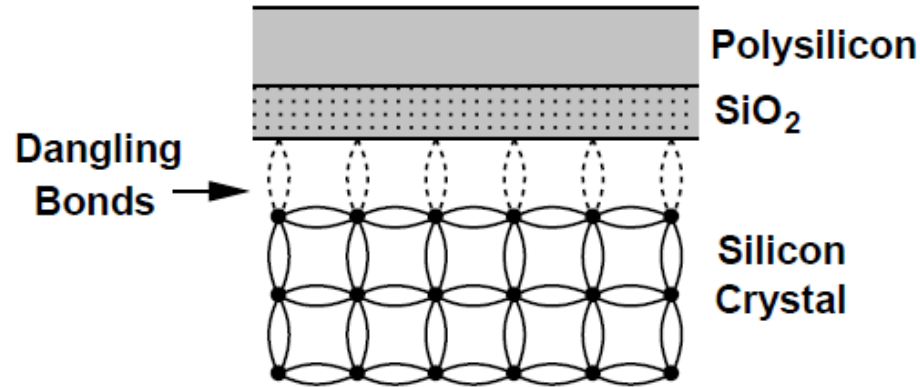


# MOSFET Thermal Noise



- Effect of  $R_G$  can be reduced by proper layout
- For total gate resistance of  $R_G$ , equivalent noise resistance is  $R_G/3$  (Distributed effects).

# Flicker Noise



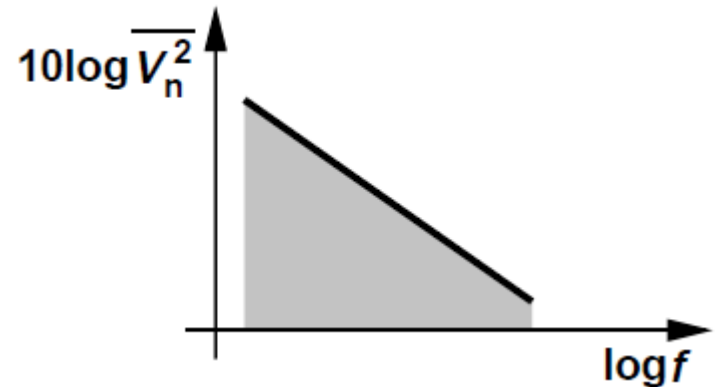
- “dangling” bonds giving rise to extra energy states
- Charge carriers moving at the interface are randomly trapped and later released by such energy states, introducing “flicker” noise in the drain current
- Depends on cleanness of oxide-silicon interface and CMOS technology

# Flicker Noise

- Modeled as a voltage source in series with the gate and in the saturation region, is roughly given by

$$\overline{V_n^2} = \frac{K}{C_{ox}WL} \cdot \frac{1}{f}$$

- $K$  is a process-dependent constant on the order of  $10^{-25} \text{ V}^2\text{F}$
- Larger Area – Averaging effect – Less Flicker*



- PMOS devices better  $1/f$  noise  
→ Holes are carried in a “buried” channel, below oxide-silicon interface

# Flicker Noise Corner Frequency

- At low frequencies, the flicker noise power approaches infinity
- Intersection point of thermal noise and flicker noise spectral densities is called “corner frequency”  $f_c$

At  $f=f_c$ ,

Thermal noise = Flicker noise. i.e.,

$$4kT\gamma g_m = \frac{K}{C_{ox}WL} \cdot \frac{1}{f_c} \cdot g_m^2$$

that is,

$$f_c = \frac{K}{\gamma C_{ox}WL} \cdot g_m \frac{1}{4kT}$$

$$f_c \approx \frac{K}{\gamma} \cdot \omega_t \cdot \frac{1}{4kT} \quad \text{and} \quad \omega_t \propto \frac{1}{L^2}$$

Hence, the  $f_c$  increases with technology scaling.

